



Diffusion of Oxygen in Ni and Fe due to Substitutional Vacancy from DFT Calculations

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First-Principles Calculation of Self-Diffusion Coefficients

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We demonstrate a first-principles method to compute all factors entering the vacancy-mediated self-diffusion coefficient. Using density functional theory calculations of fcc Al as an illustrative case, we determine the energetic and entropic contributions to vacancy formation and atomic migration. These results yield a quantitative description of the migration energy and vibrational prefactor via transition state theory. The calculated diffusion parameters and coefficients show remarkably good agreement with experiments. We provide a simple physical picture for the positive entropic contributions.

- Use density functional theory calculations to determine the energetic and entropic contributions to vacancy formation and atomic migration, i.e. all parameters used to evaluate vacancy-mediated diffusion coefficients
- Compare the calculated values with available experimental data

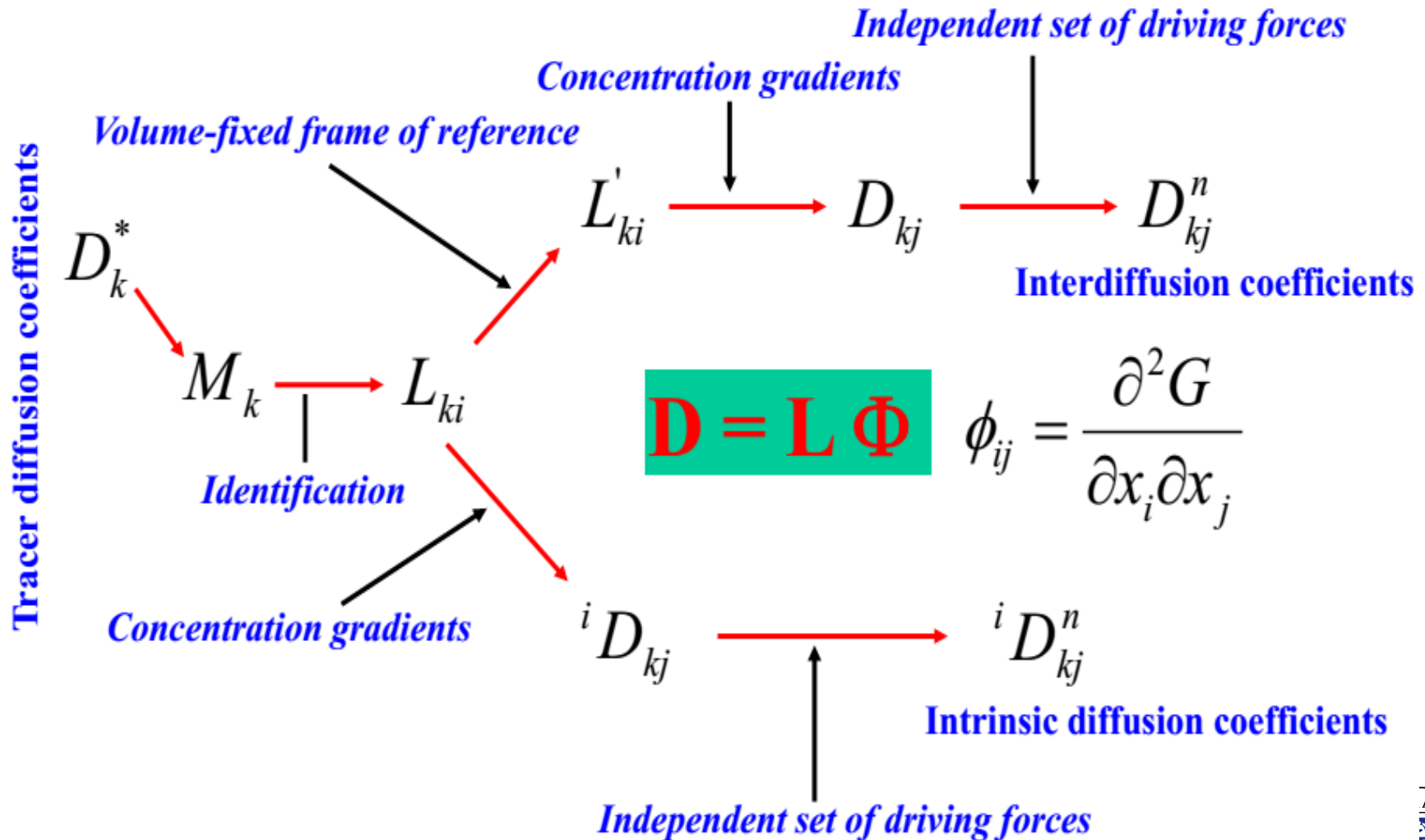


Outline

- **Interstitial diffusion from first-principles**
 - Theory and finite temperature thermodynamics
- **Oxygen diffusion in fcc nickel**
 - Site preference & diffusion pathway
 - Va-modified site preference & diffusion path
 - Oxygen diffusivity with and without Va
- **Oxygen diffusion in bcc iron**
 - Site preference with and without Va
 - Oxygen diffusivity with and without Va
- **Summary**



Diffusion coefficient **D** is a product of kinetic coefficient **L** and thermodynamic factor **Φ**





Interstitial diffusion equation

Following Wert & Zener, interstitial diffusivity can be described by:

Coordinate number Jump distance
 $D = n \beta d^2 \Gamma$
Probability factor Jump frequency

$$\Gamma = \frac{kT}{h} \frac{Z_{TS}}{Z_{IS}} e^{-\Delta E/kT} = \frac{kT}{h} \frac{\prod_{i=1}^{3N-3} \left[2 \sinh \left(\frac{h \nu_i^{IS}}{2kT} \right) \right]}{\prod_{i=1}^{3N-4} \left[2 \sinh \left(\frac{h \nu_i^{TS}}{2kT} \right) \right]} e^{-\Delta E/kT}$$

High temperatures ($h\nu/2kT \ll 1$)
 \Rightarrow **Vineyard** equation

$$\Gamma = \frac{\prod_{i=1}^{3N-3} \nu_i^{IS}}{\prod_{i=1}^{3N-4} \nu_i^{TS}} e^{-\Delta E/kT} = \nu^* e^{-\Delta E/kT}$$

Low temperatures ($h\nu/2kT \gg 1$)
 \Rightarrow **Eyring** equation

$$\Gamma = \frac{kT}{h} \frac{\exp \sum_{i=1}^{3N-3} \frac{h \nu_i^{IS}}{2kT}}{\exp \sum_{i=1}^{3N-4} \frac{h \nu_i^{IS}}{2kT}} e^{-\Delta E/kT} = \frac{kT}{h} e^{-(\Delta E + \Delta G_{vib})/kT}$$

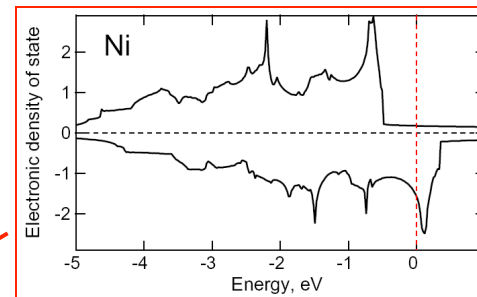
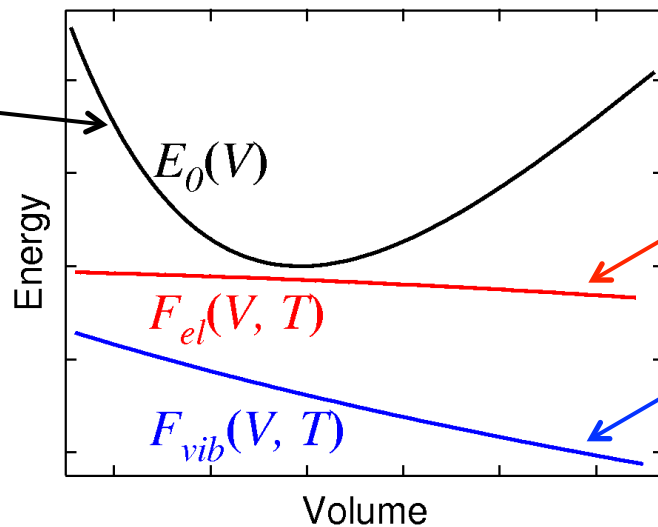


Finite temperature thermodynamics - The quasiharmonic approach

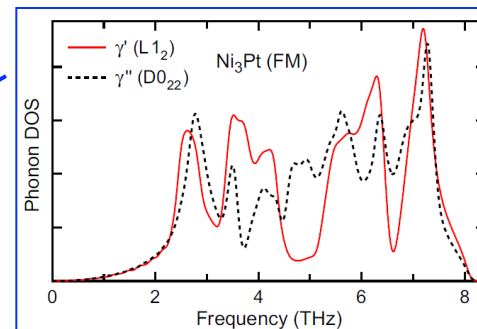
$$F(V, T) = E_0(V) + F_{vib}(V, T) + F_{el}(V, T)$$

- $E_0(V)$ Static energy at 0 K and volume V , i.e., EOS (by VASP)
- $F_{vib}(V, T)$ Vibrational contribution at V & T (Phonon or Debye model)
- $F_{el}(V, T)$ Thermal electronic contribution at V & T (by VASP)

DFT directly



E-DOS



P-DOS

Calculation methods –

O in fcc Ni & O in bcc Fe

- DFT based first-principles calculations
 - VASP code
 - PAW method for electron-ion interaction
 - Exchange-correctional (X-C) functionals
 - LDA for O in fcc Ni
 - GGA-PBE for O in Fe
 - Also tested others: PW91, PBE+U, PBEsol, AM05
 - CI-NEB for migration barrier calculations
 - Phonon & Debye model for finite T thermodynamics



Case 1 of 2

- **Oxygen diffusion in fcc Ni with and without vacancy**

Oxygen diffusion in fcc Ni

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First-principles studies on vacancy-modified interstitial diffusion mechanism of oxygen in nickel, associated with large-scale atomic simulation techniques

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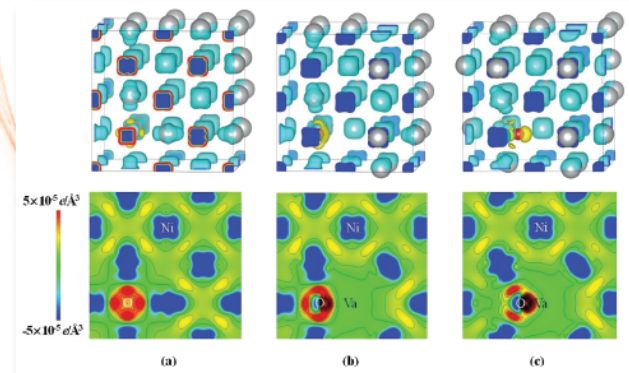
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This paper is concerned with the prediction of oxygen diffusivities in *fcc* nickel from first-principles calculations and large-scale atomic simulations. Considering only the interstitial octahedral to tetrahedral to octahedral minimum energy pathway for oxygen diffusion in *fcc* lattice, greatly underestimates the migration barrier and overestimates the diffusivities by several orders of magnitude. The results indicate that vacancies in the Ni-lattice significantly impact the migration barrier of oxygen in nickel. Incorporation of the effect of vacancies results in predicted diffusivities consistent with available experimental data. First-principles calculations show that at high temperatures the vacancy concentration is comparable to the oxygen solubility, and there is a strong binding energy and a redistribution of charge density between the oxygen atom and vacancy. Consequently, there is a strong attraction between the oxygen and vacancy in the Ni lattice, which impacts diffusion. © 2014 AIP Publishing LLC. [<http://dx.doi.org/10.1063/1.4861380>]



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Oxygen diffusion in fcc Ni – site preference

Solution energy:

For interstitial solution:

$$E_O^{\text{sol}} = E_{n\text{Ni}+\text{O}} - E_{n\text{Ni}} - E_{\text{O}},$$

For substitutional solution: $E_O^{\text{sol}} = E_{(n-1)\text{Ni}+\text{O}} - \frac{n-1}{n}E_{n\text{Ni}} - E_{\text{O}}$

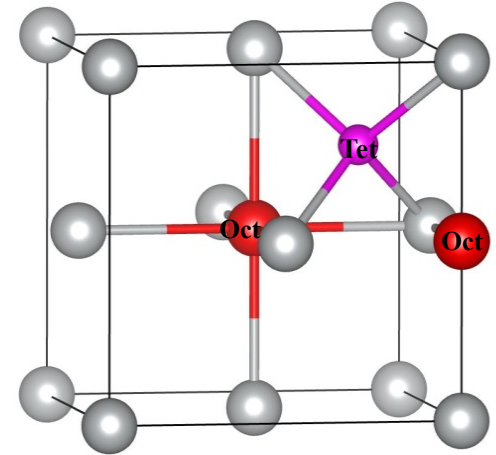
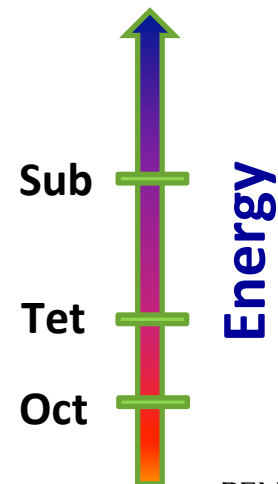


TABLE I. Solution energies (eV) of oxygen in pure nickel.

Substitutional	Interstitial		Method
	Octahedral	Tetrahedral	
E_O^{sol}	-2.31	-3.28	This work
	-2.65, ^a -3.39 ^b	-2.38 ^a	Other DFT

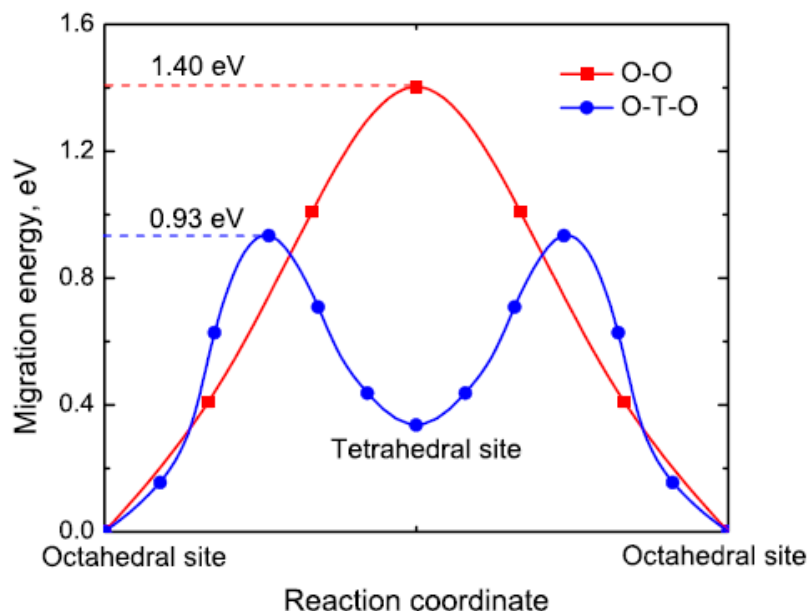
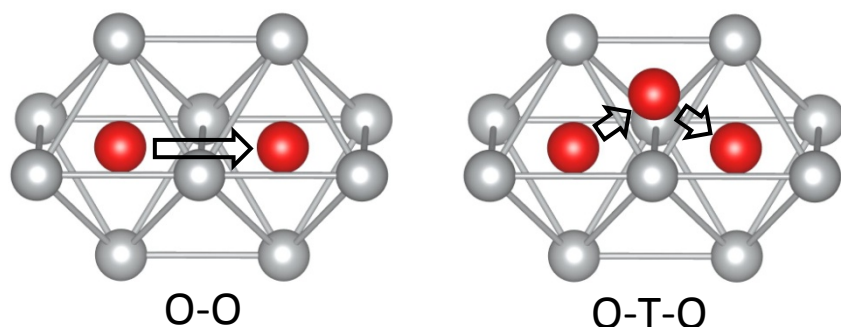
^a E. H. Megchiche, et al, JPCM 19 (2007) 296201

^b J. J. Kim, et al, APL 100 (2012) 131904



Oxygen diffusion in fcc Ni – diffusion pathway

- Two migration pathways are considered

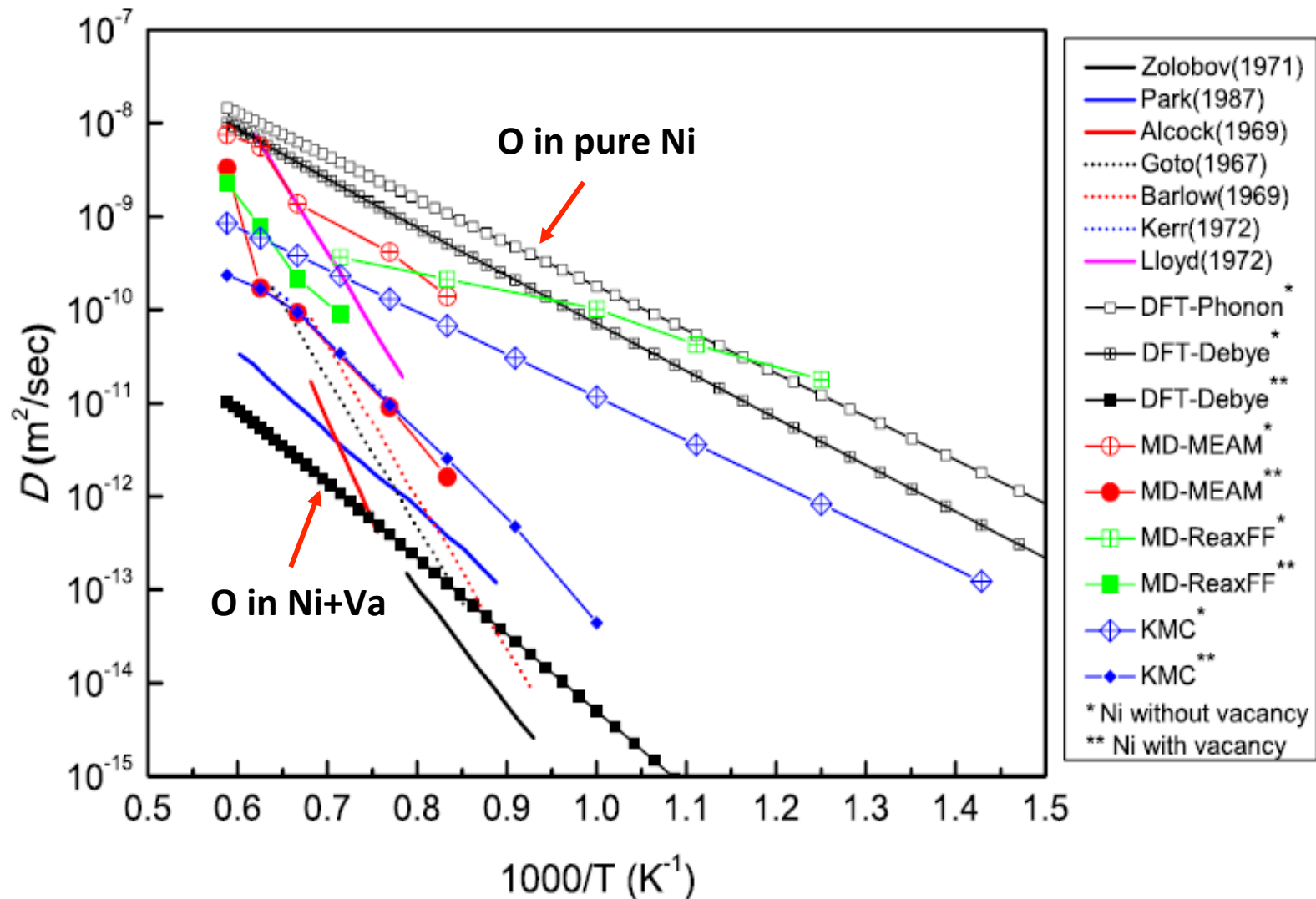


	O-O	O-T-O
This work	1.40	0.93
Other DFT	1.57	1.23
	1.44	1.12
Experiment	1.70, 3.20, 3.12, 3.08, 4.28, 2.49, 1.89	

Predicted barriers much
lower than measurements



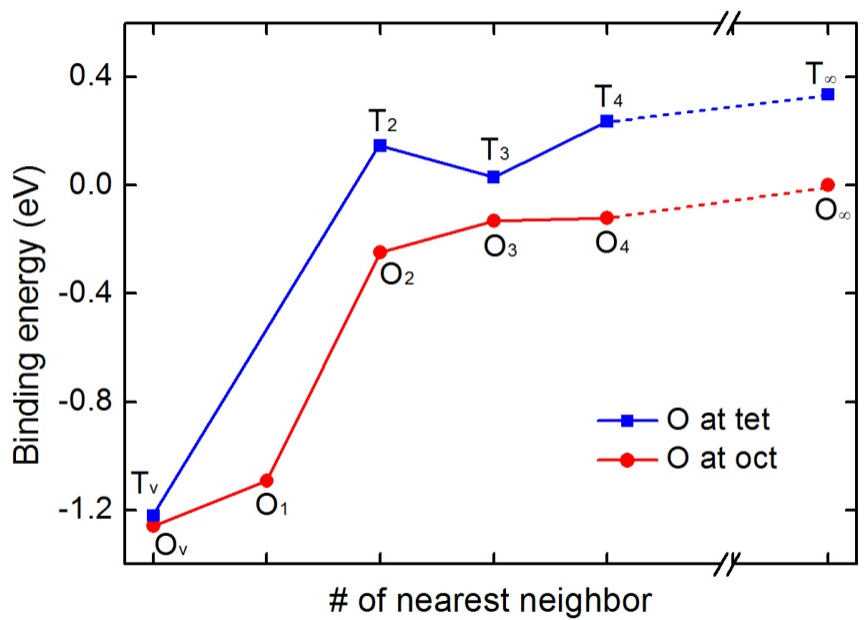
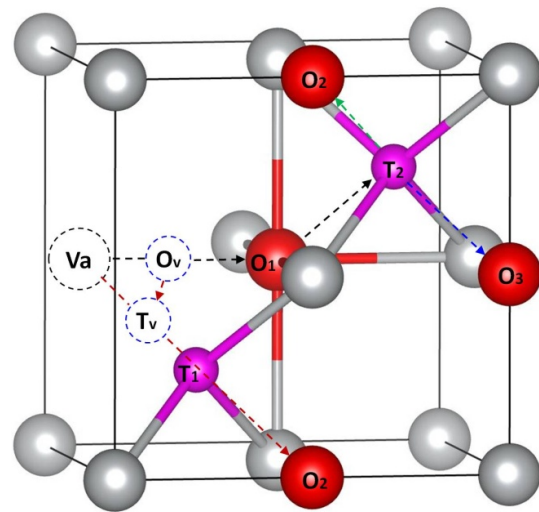
Oxygen diffusion in fcc Ni – finite T diffusivity



Oxygen diffusion in fcc Ni – vacancy modified site preference

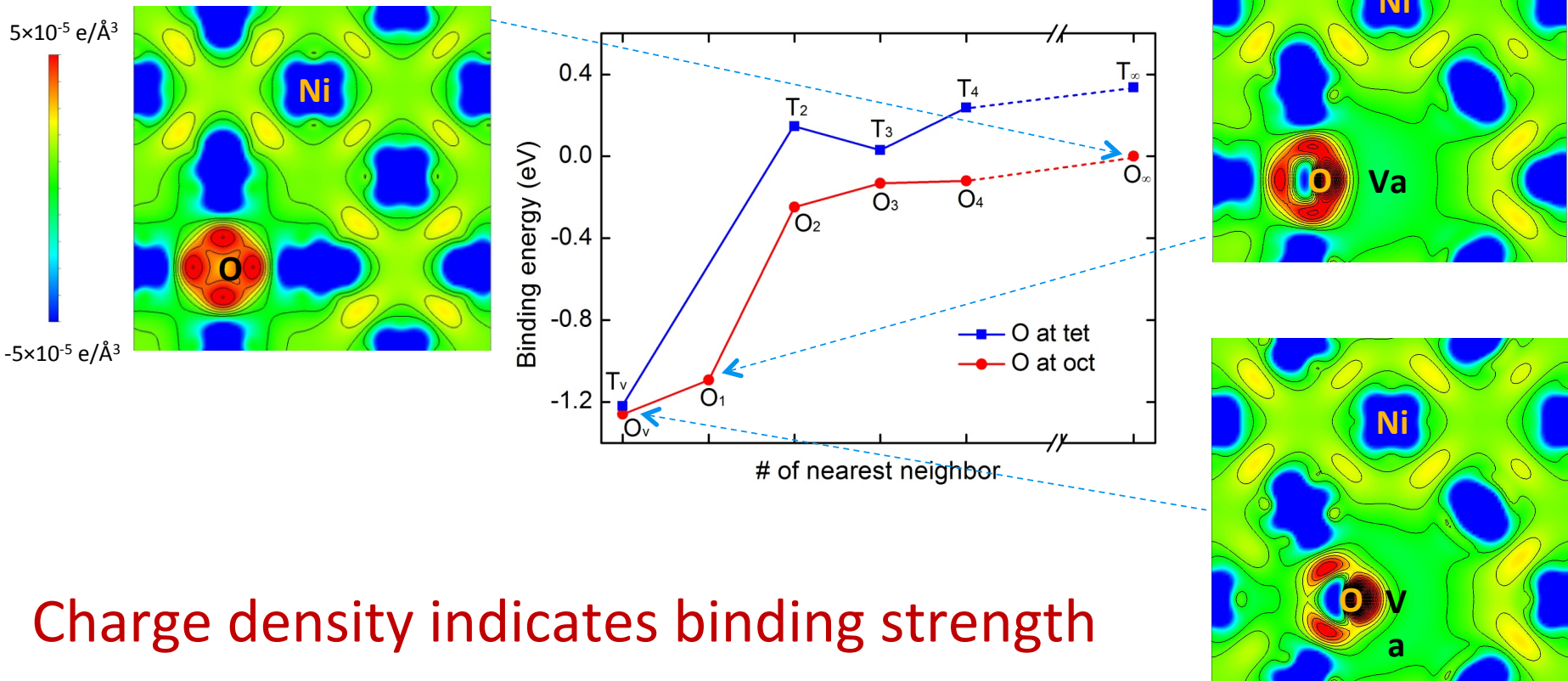
- With Va, the neighboring Oct & Tet sites shift, *i.e.*:

$$O_1 \rightarrow O_v; T_1 \rightarrow T_v$$



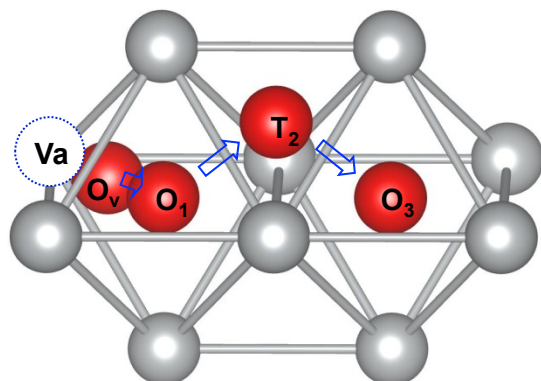
- O-Va binding energy ~1.2 eV.
- Effect up to the 3rd NN (O₃).

Oxygen diffusion in fcc Ni – binding energy of O and Va

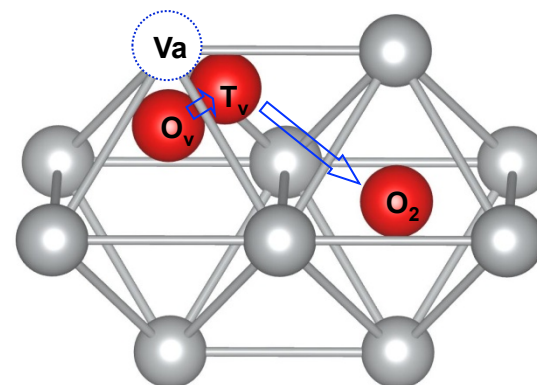


Oxygen diffusion in fcc Ni – Va modified diffusion pathway

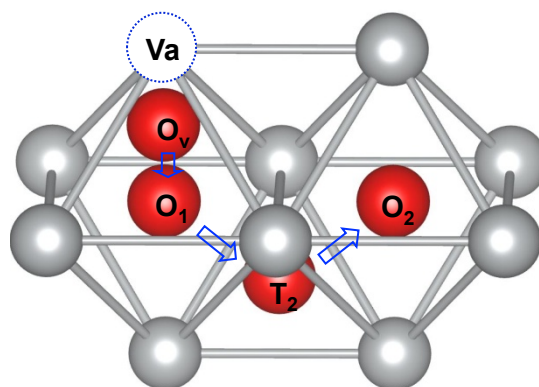
- Three possible paths for O diffusion from Va



(a) $O_v - O_1 - T_2 - O_3$



(b) $O_v - T_v - O_2$



(c) $O_v - O_1 - T_2 - O_2$

Oxygen diffusion in fcc Ni – Va modified diffusion barrier

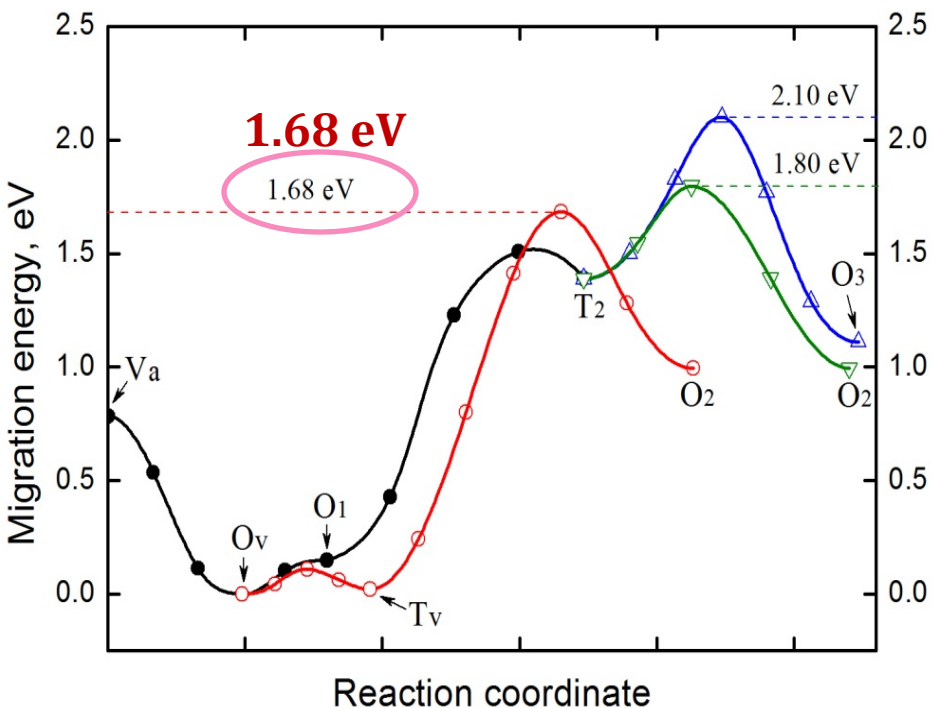


TABLE II. Migration energies (eV) of oxygen in nickel without and with vacancy effect.

	<i>O-O</i>	<i>O-T-O</i>	Method
E_O^{mig}	1.40 ^a 1.57, ^c 1.44 ^d	0.93, ^a 1.68, ^b 1.80, ^b 2.10 ^b 1.23, ^c 1.12 ^d 1.99 ^e	This work Other DFT Other MD
	1.70, ^f 1.89, ^g 3.08, ^h 2.49, ⁱ 3.2, ^j 4.28, ^k 3.12 ^l		Experiment

^aNi without vacancy.

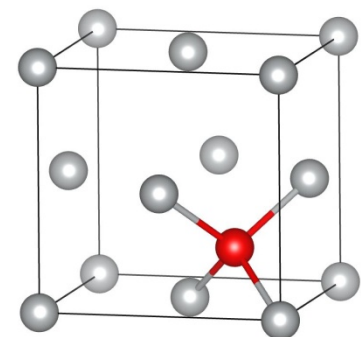
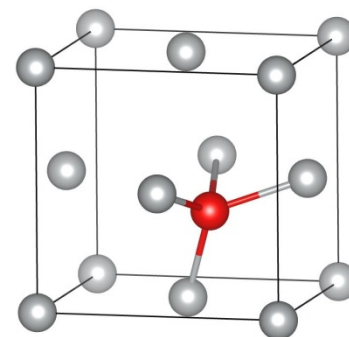
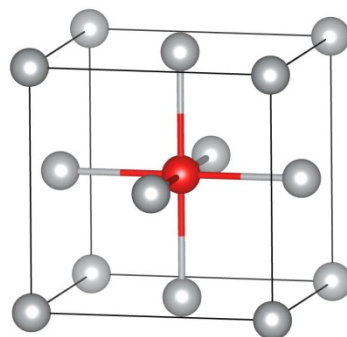
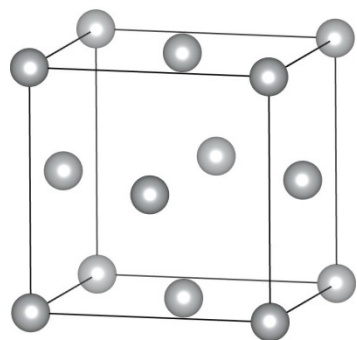
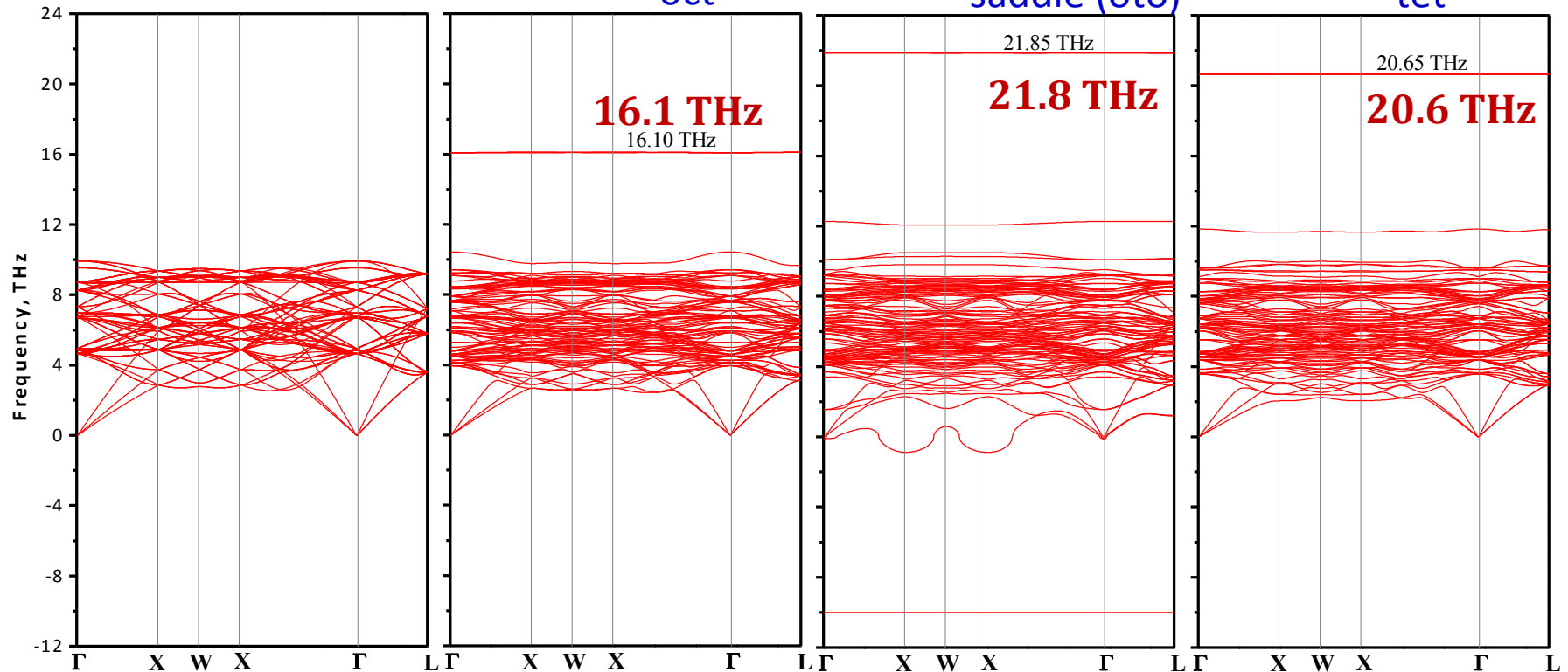
^bNi with vacancy.

Significant increase of diffusion barrier from 0.93 to 1.68 eV

Oxygen diffusion in fcc Ni - **phonon**

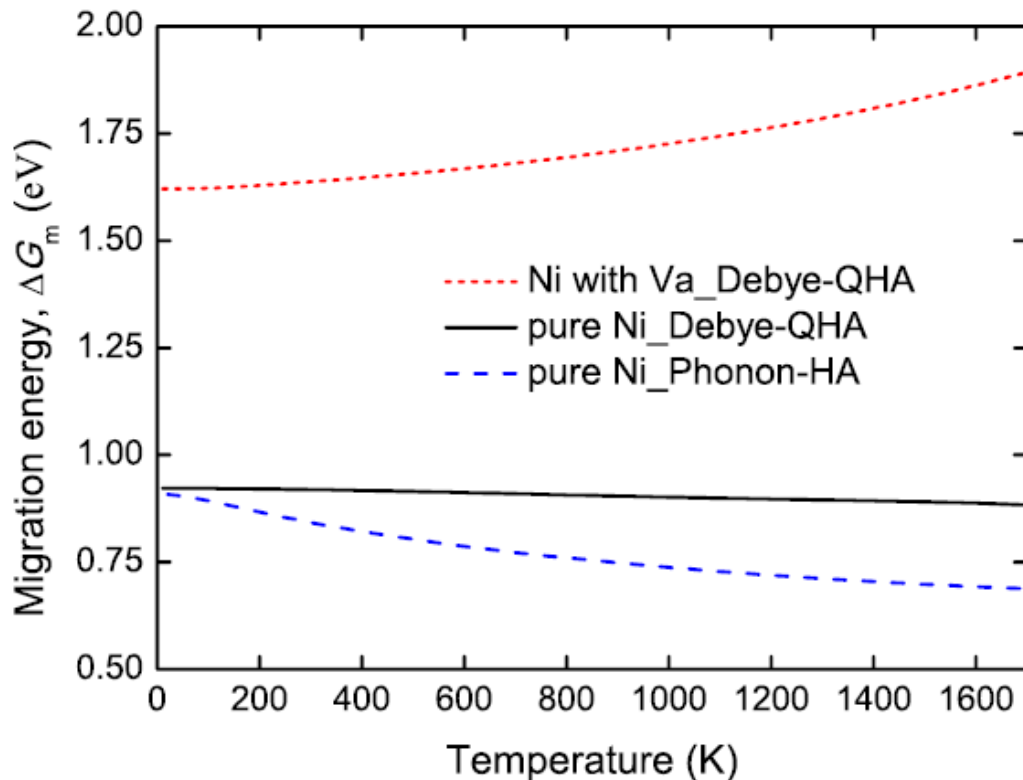


Pure Ni

Ni-O_{oct}Ni-O_{saddle (oto)}Ni-O_{tet}



Oxygen diffusion in fcc Ni – migration barrier at finite T



Jump frequency:

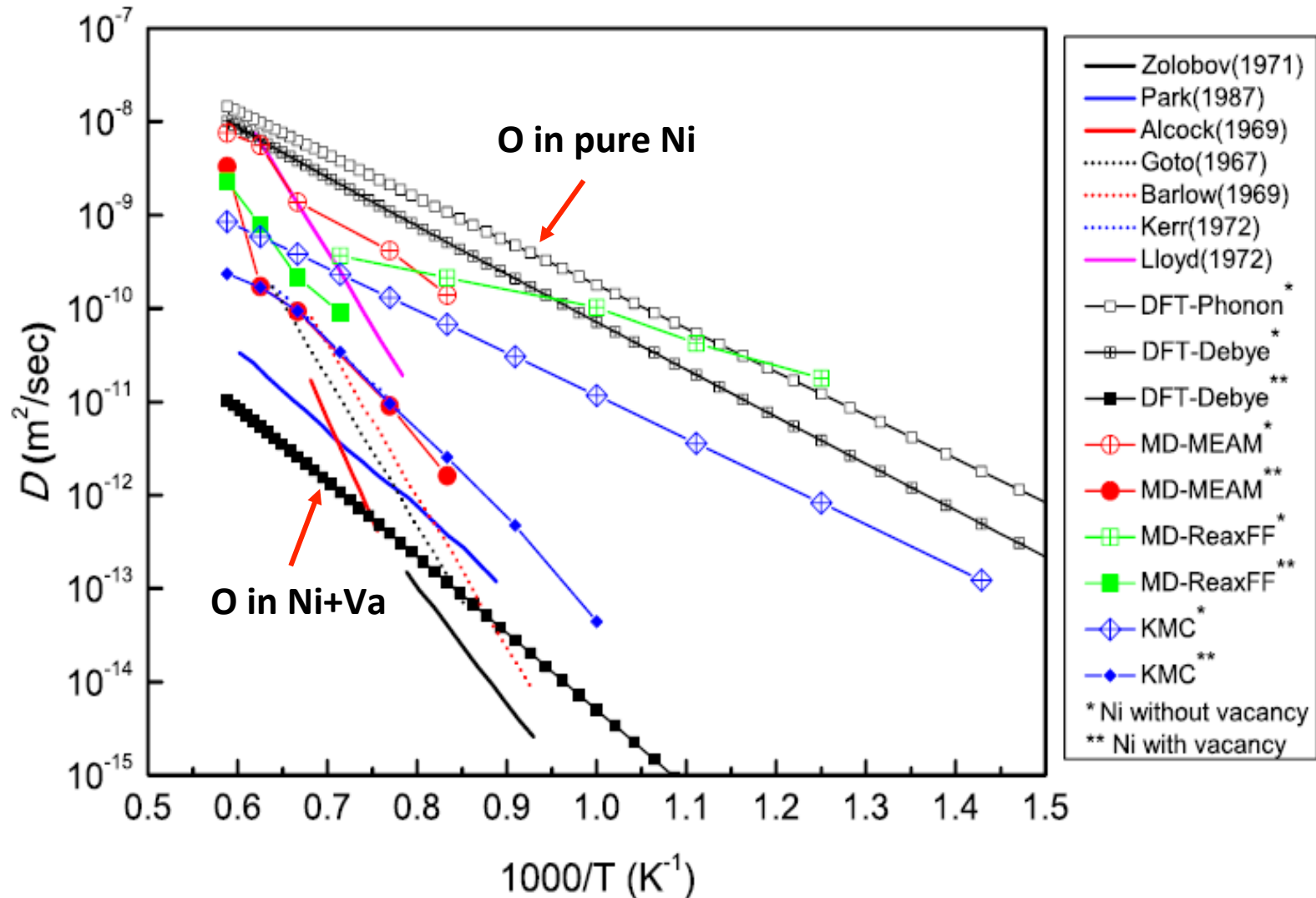
$$\Gamma = \frac{kT}{h} e^{-\Delta G_m / kT}$$

- **Phonon:** accurate but expensive
- **Debye:** efficient but less expensive

Migration free energies for O_v - T_v - O_2 pathway



Oxygen diffusion in fcc Ni – finite T diffusivity





Oxygen diffusion in fcc Ni –

Arrhenius parameters $D = D_0 \exp(-Q / kT)$

TABLE III. Diffusion constants D_0 and activation energies Q predicted by different computational methods in comparison with available experimental data.

D_0 (m ² /s)	Q (eV)	T (K)	Method	Ref.
8.0×10^{-6}	0.92	700–1700	DFT-Phonon ^a	This work
7.4×10^{-6}	0.98	700–1700	DFT-Debye ^a	This work
4.3×10^{-7}	0.91	700–1700	kMC ^a	This work
6.4×10^{-6}	0.95	1200–1700	MD-MEAM ^a	This work
2.3×10^{-8}	0.49	800–1400	ReaxFF ^a	This work
8.8×10^{-7}	1.64	700–1700	DFT-Debye ^b	This work
3.9×10^{-4}	1.82	1000–1700	kMC ^b	This work
2.8×10^{-4}	1.95	1200–1700	MD-MEAM ^b	This work
9.5×10^{-3}	2.25	1000–1400	ReaxFF ^b	This work
4.9×10^{-6}	1.70	1123–1673	Potentiometric	Park and Altstetter, 1987
7.9	3.20	1073–1473	Internal oxidation	Barlow and Grundy, 1969
1.82	3.12	1173–1573	Internal oxidation	Goto <i>et al.</i> , 1967
26.8	3.08	1273–1623	Internal oxidation	Lloyd and Martin, 1972
8.93×10^3	4.28	1323–1473	Gravimetric	Alcock and Brown, 1969
1.21×10^{-3}	2.49	623–1273	Desorption	Zholobov and Malev, 1971
2.06×10^{-4}	1.89	1273–1573	Electrochemistry	Kerr, 1972

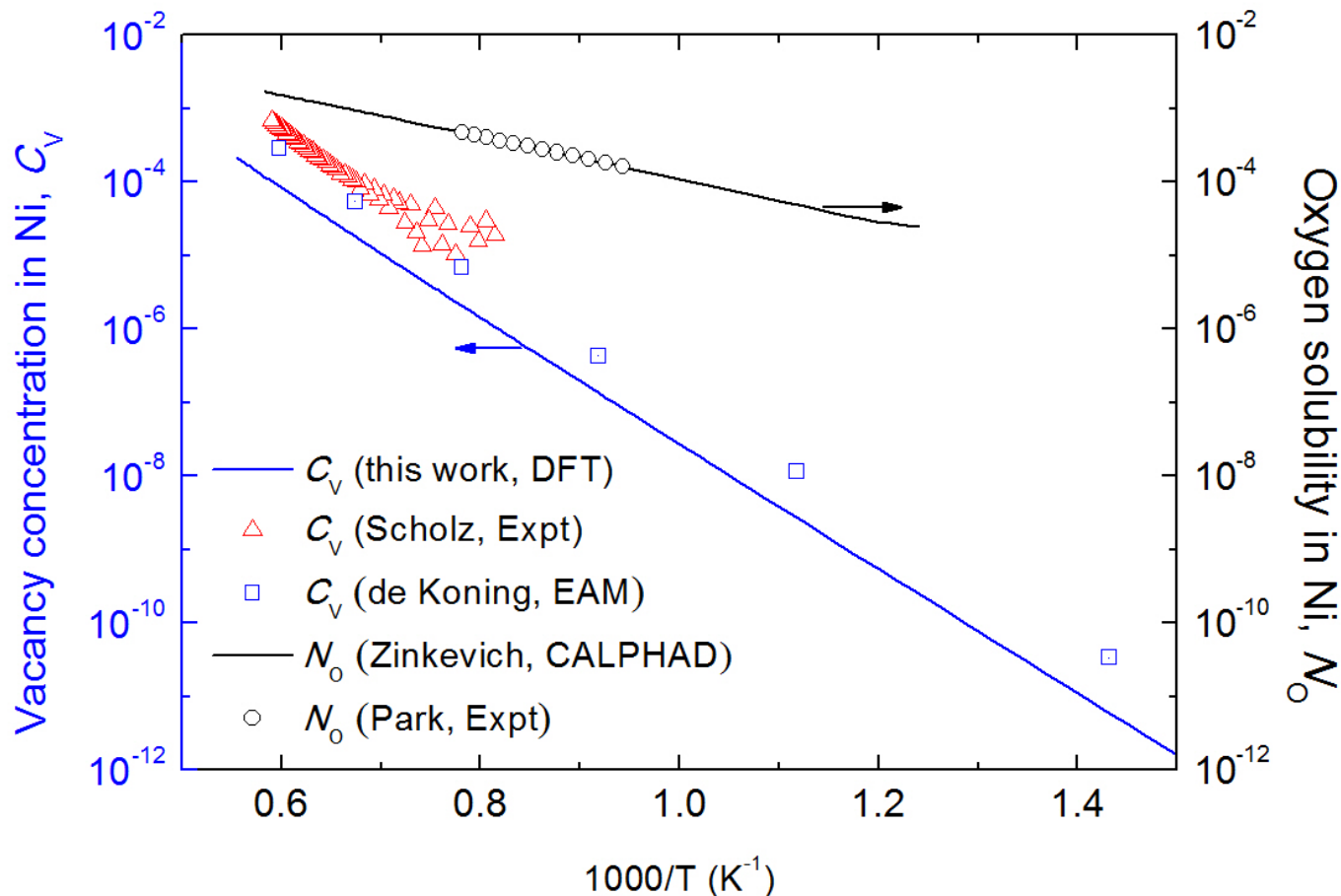
^aNi without vacancy.

^bNi with vacancy.

D_0 : $8.8 \times 10^{-7} \sim 9.5 \times 10^{-3}$ (Expt: $4.9 \times 10^{-6} \sim 8.93 \times 10^3$)

Q : $1.64 \sim 2.25$ (Expt: $1.7 \sim 4.28$)

Discussion – equilibrium O & Va contents in Ni



Vacancy concentration vs. oxygen solubility in Ni



Case 2 of 2

- **Oxygen diffusion in bcc Fe with and without vacancy**



Oxygen diffusion in bcc Fe

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Vacancy mechanism of oxygen diffusivity in bcc Fe: A first-principles study



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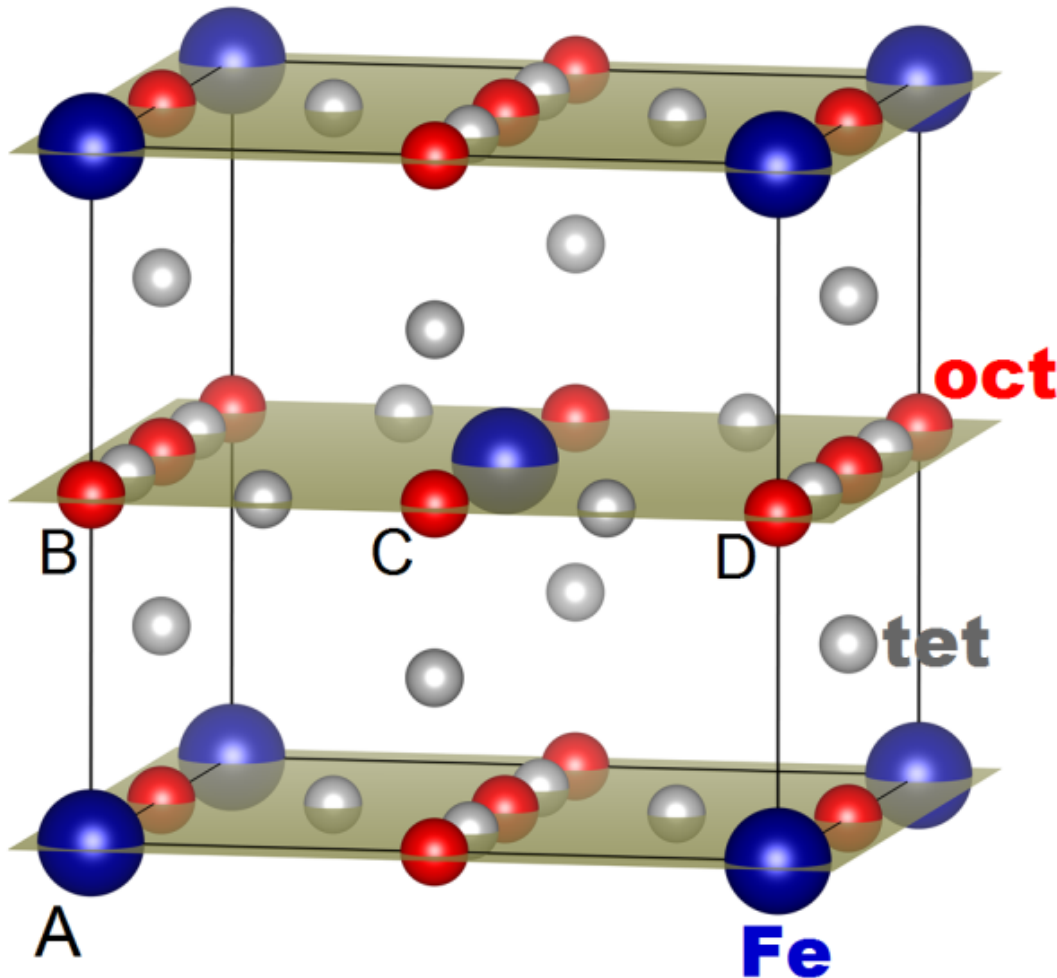
ABSTRACT

Diffusivity of interstitial oxygen (O) in bcc iron (Fe) with and without the effect of vacancy has been investigated in terms of first-principles calculations within the framework of transition state theory. Examination of migration pathway and phonon results indicates that O in octahedral interstice is always energetically favorable (minimum energy) with and without vacancy. It is found that vacancy possesses an extremely high affinity for O in bcc Fe, increasing dramatically the energy barrier (~80%) for O migration, and in turn, making the predicted diffusion coefficient of O in bcc Fe in favorable accord with experiments.



bcc Fe & its oct & tet interstitial sites

– structure



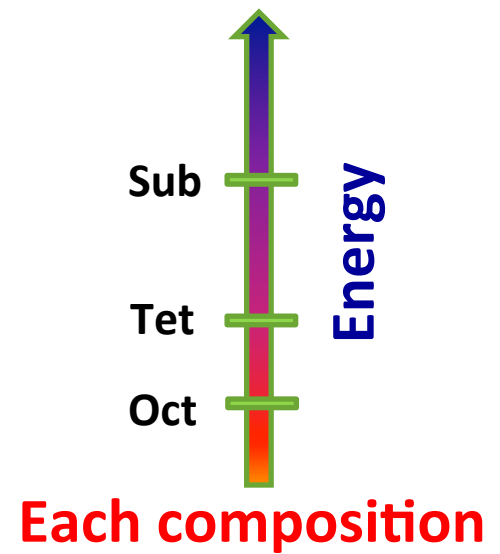
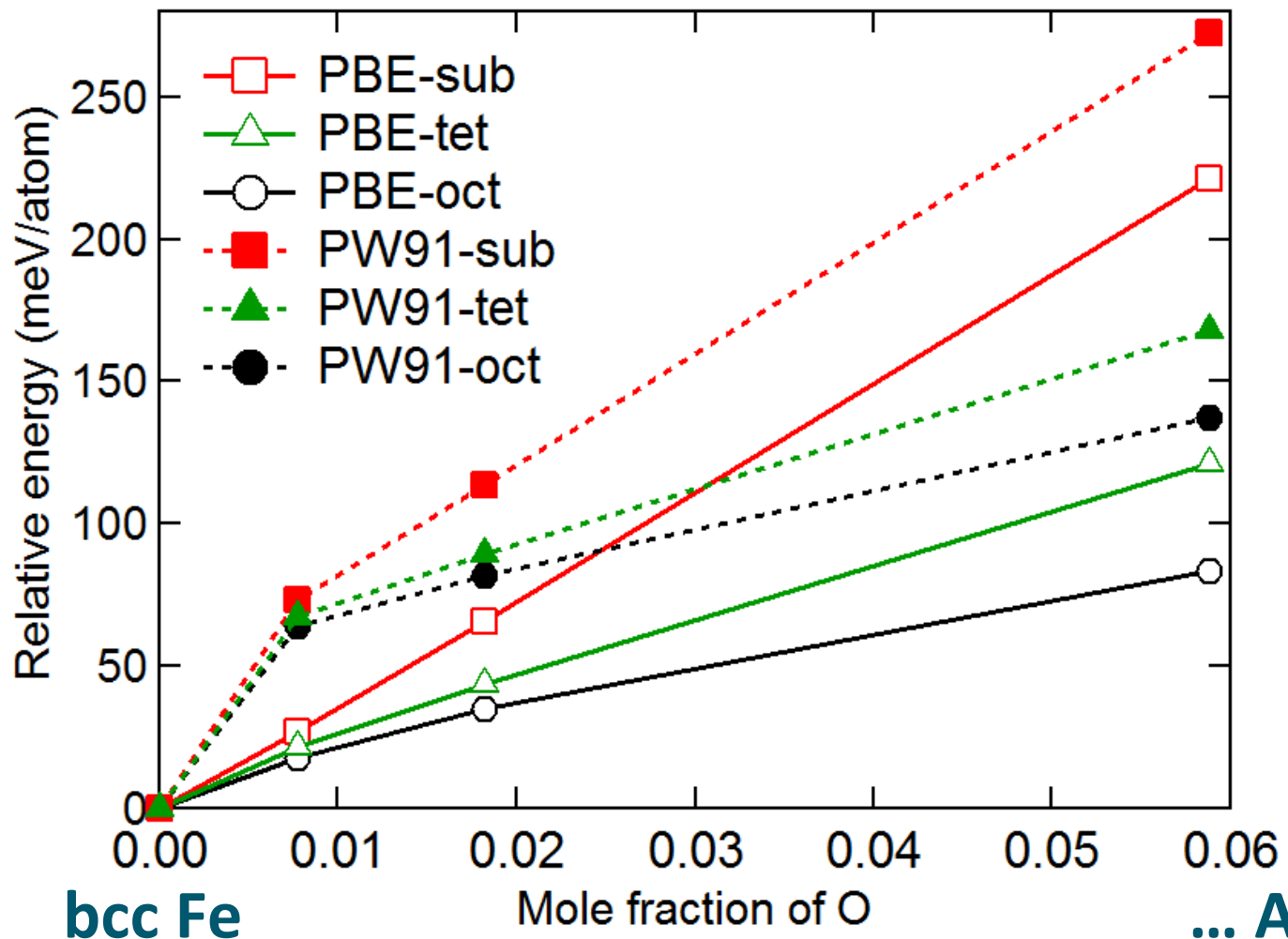
Fe: **2a** (0, 0, 0)

O-oct: **6b** (0 ½ ½)

O-tet: **12d** (0 ½ ¼)

Site preference of O in bcc Fe

– w.r.t. bcc Fe and AFM α -Fe₂O₃



bcc Fe

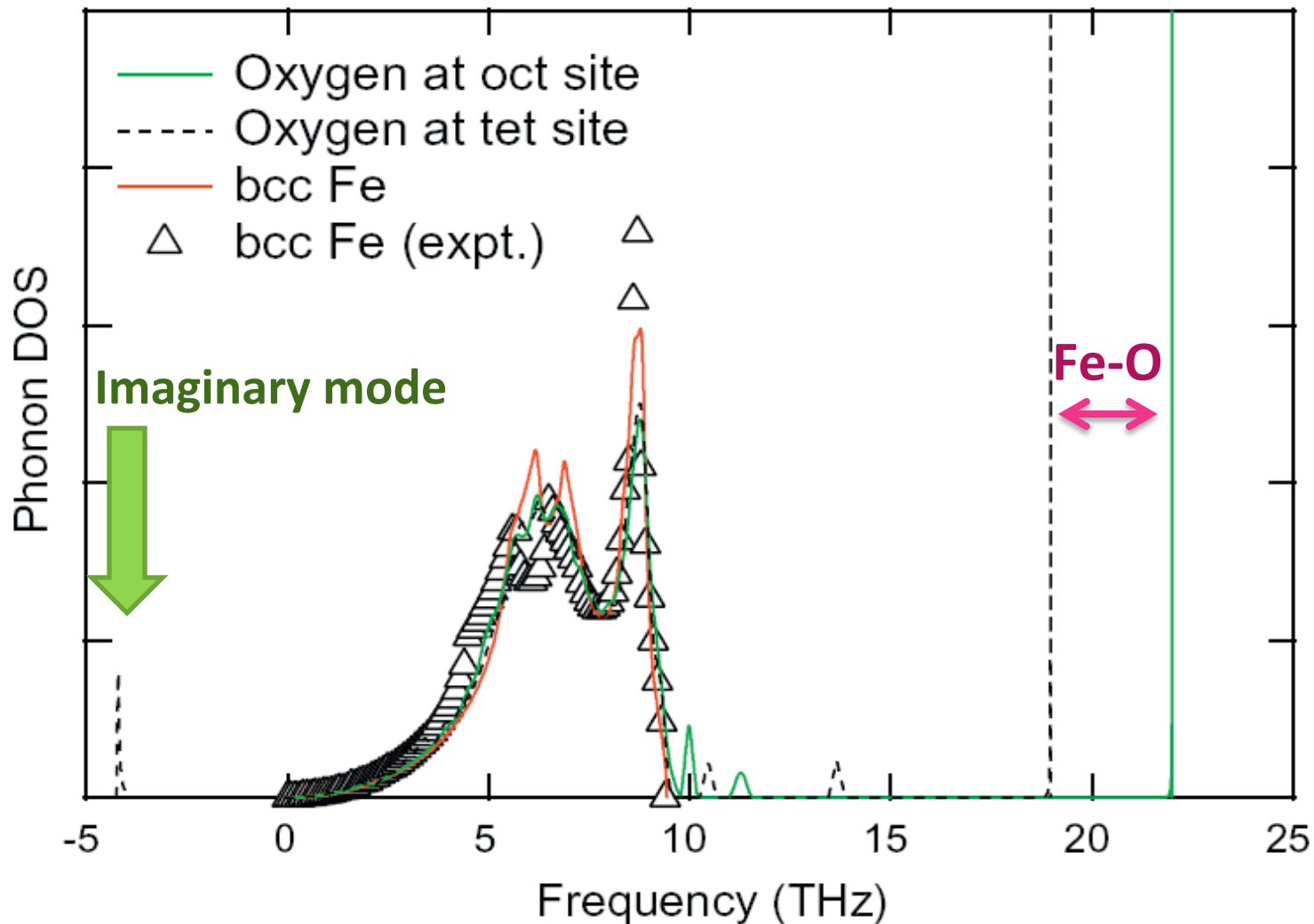
Mole fraction of O

... AFM Fe₂O₃ PENNSTATE

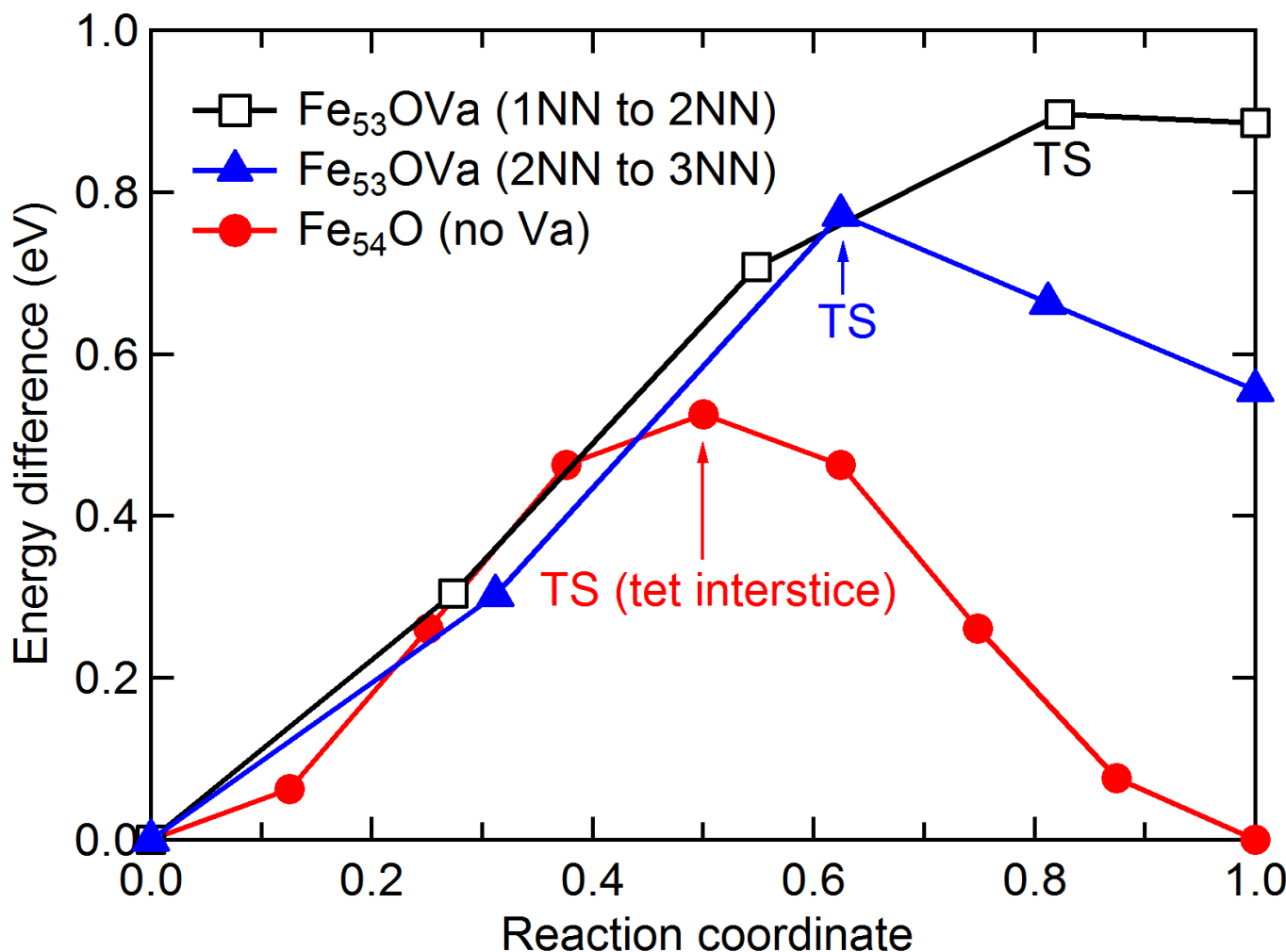
Phonon DOS of bcc Fe (without Va)



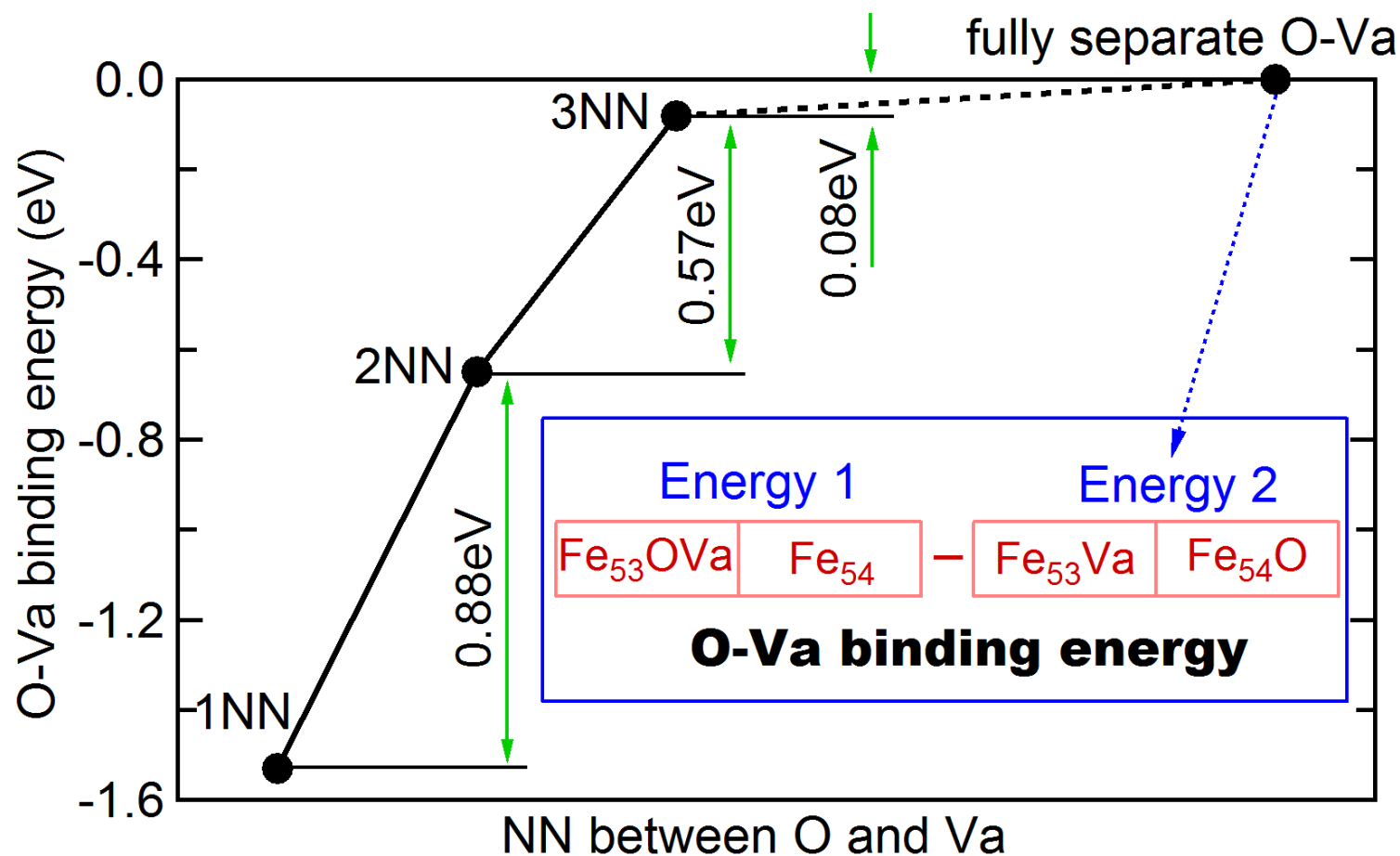
– **0 at oct & tet sites**



Minimum energy pathways of O diffusion in bcc Fe **with/without Va**



O-Va binding energy in bcc Fe - using the $3 \times 3 \times 3$ supercell





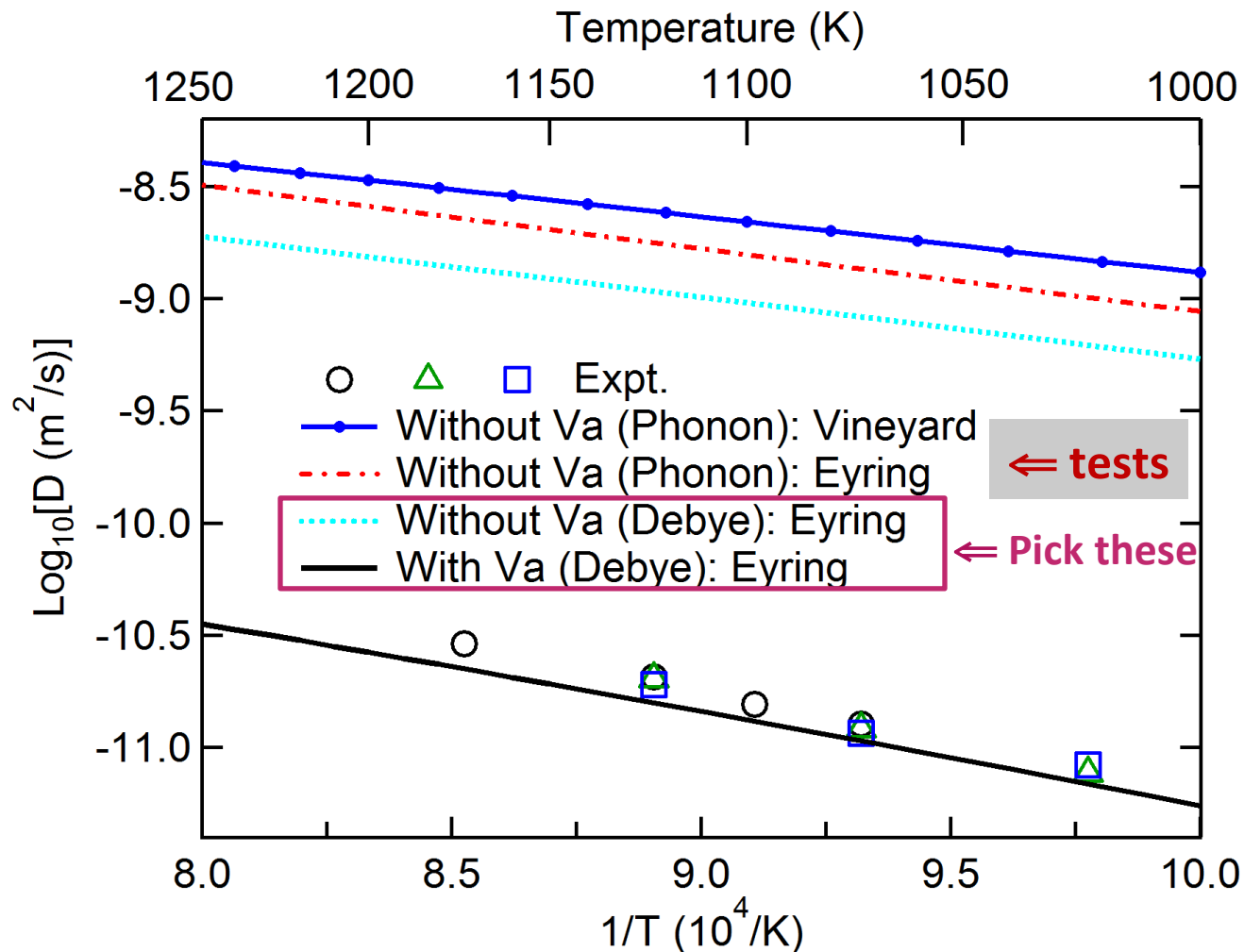
Activation energy of O diffusion in bcc Fe - energy (kJ) between oct & tet sites

PW91: 2×2×2 cell	49.8	PBEsol: 3×3×3 cell	39.1
PW91: 3×3×3 cell	38.8	PBE-CINEB-bulk-relax (O-T)	51.4
PW91: 4×4×4 cell	38.9	PBE-CINEB-bulk-relax (O-T-O)	49.6
PBE: 2×2×2 cell	61.5	PBE-CINEB-bulk-fix (O-T-O)	52.1
PBE: 3×3×3 cell	47.0	PBE-CINEB-relax- Va (O-T-O)	98.8
PBE: 4×4×4 cell	47.8	Expt.: Swisher 1967	177
PBE: 3×3×3 (charged)	51.9	Expt.: Barlow 1969	167
LDA: 3×3×3 cell	16.1	Expt.: Takada 1986	86±6
			90±7



Arrhenius plots of O diffusion in bcc Fe

with/without Va $D = D_0 \exp(-Q / kT)$





Arrhenius plots of O diffusion in bcc Fe with/without Va (details)

$$D = D_0 \exp(-Q / kT)$$

System	ΔE_m	D_0	Q
Fe ₅₄ O (without Va) ^a	0.526 ^b	$3.75 \times 10^{-7(e)}$	0.49 ^e
	0.503 ^c	$5.72 \times 10^{-7(f)}$	0.56 ^f
		$2.86 \times 10^{-7(g)}$	0.54 ^g
Fe ₅₃ O Va (1NN to 2NN) ^a	0.897 ^b	$0.63 \times 10^{-7(g)}$	0.80 ^g
	0.892 ^d		
Fe ₅₃ O Va (2NN to 3NN) ^a	0.772 ^b		
Expt: O in dilute Al-Fe ^h		$(1.79^{+1.76}_{-0.89}) \times 10^{-7}$	0.89 ± 0.06
Expt: O in dilute Si-Fe ^h		$(2.91^{+3.40}_{-1.57}) \times 10^{-7}$	0.93 ± 0.07
Expt: O in dilute Ti-Fe ^h		$(3.78^{+3.55}_{-1.83}) \times 10^{-7}$	0.95 ± 0.06
Expt: O in dilute Si-Fe ⁱ		$(400 \pm 100) \times 10^{-7}$	1.73 ± 0.01
Expt: O in dilute Al-Fe ^j		37.2×10^{-7}	1.01
Expt: estimated values ^k			0.98 ± 0.1

without

with

Expt



Summary

- Exploration of site preference, diffusion pathways & barriers, and diffusivities of oxygen
- Existence of strong O-Va binding energy in metals
- Va-modified interstitial diffusion mechanism proposed to quantitatively predict diffusivity of oxygen in metals
- Case studied in fcc Ni and bcc Fe